# Allpix2 General





# **Simulation pipeline**



# **Deposited charge**

- The number of electron/hole pairs created is calculated using the mean pair creation energy in sapphire (27 eV) []]. Fluctuations are modeled using a Fano factor (0.115) assuming Gaussian statistics. [2]
- As first approximation of the initial particle beam, a gaussian beam was used. Its parameters were extracted fitting the realistic beam from Ptarmigan.
- Accurate reproduction of the initial beam can be implemented, in an analogous manner of what done in Geant4 StandaloneGBP. This requires 10 days of work (not spoiling multi-threading requires special care)

 The external electrostatic field in the detector – i.e. not including polarisation effects produced during charge transport – can be calculated numerically with a tool which comes with allpix2. The computation needs to be made once and it takes 12/24 hours.

Detector geometry and the bias voltage are the inputs of the E-field computation. The output is a INIT/APF file (the former is compatible with PixeIAV) with a 3d map of the vector field.

- The electrostatic field is imported via the "ElectricFieldReader" module which allows to implement the E field either with a constant/parametric formula or by reading the E field from a file.
- At present time, for the preliminary simulation a constant E field of intensity 5 V/um is used. Polarisation effects – e.g. local E-field produced by trapped charges – are not accounted yet. They may be encompassed by using a E-field profile quadratic in the sensor thickness z (as done in ref. []])

### **Charge carrier propagation**

- The [DepositionGeant4] module produces charge carriers.
- Electrons & holes are then propagated toward the collecting implants with a drift/diffusion model.
- Jacoboni-Canali model is the one used.
- Default silicon parameters are replaced with the sapphire parameters from [1] e [3]. Some adaptations were needed since the two models are different

#### 6.1.1 Jacoboni-Canali Model

The Jacoboni-Canali model  $\boxed{25}$  is the most widely used parametrization of charge carrier mobility in Silicon as a function of the electric field E. It has originally been derived for  $\langle 111 \rangle$ silicon lattice orientation, but is widely used also for the common  $\langle 100 \rangle$  orientation. The mobility is parametrized as

$$\mu(E) = \frac{v_m}{E_c} \frac{1}{\left(1 + (E/E_c)^{\beta}\right)^{1/\beta}},\tag{6.1}$$

where  $v_m$ ,  $E_c$ , and  $\beta$  are phenomenological parameters, defined for electrons and holes respectively. The temperature dependence of these parameters is taken into account by scaling them with respect to a reference parameter value as

$$A = A_{ref} \cdot T^{\gamma} \tag{6.2}$$

where  $A_{ref}$  is the reference parameter value, T the temperature in units of K, and  $\gamma$  the temperature scaling factor.

The parameter values implemented in Allpix<sup>2</sup> are taken from Table 5 of [25] as:

$$v_{m,e} = 1.53 \times 10^9 \cdot T^{-0.87} \,\mathrm{cm/s} \qquad v_{m,h} = 1.62 \times 10^8 \cdot T^{-0.52} \,\mathrm{cm/s}$$
  

$$E_{c,e} = 1.01 \cdot T^{1.55} \,\mathrm{V/cm} \qquad E_{c,h} = 1.24 \cdot T^{1.68} \,\mathrm{V/cm}$$
  

$$\beta_e = 2.57 \times 10^{-2} \cdot T^{0.66} \qquad \beta_h = 0.46 \cdot T^{0.17}$$

for electrons and holes, respectively.

- From reference 3 one reads...
  - the room temperature mobility of electrons (holes) as \mu\_e \sim 600 cm2/Vs (\mu\_h = 60)
  - that at 40K the e^- mobility is \simeq 30000 cm2/Vs in high purity sapphire (in Si it holds \mu = AT^{-\gamma} with A=1.43 \cdot 10^9 and \gamma=2.42 for temperatures T \geq 50 K )
  - that *impurities play a role* constraining chg. mobility to \sim 4000 cm2/Vs
- In reference []]...
  - polarisation effects, i.e. internal electric field produced by trapped charges, are accounted using a resulting electric field with parabolic shape ( $E = A(y-d/2)^2 + B$ )
  - the drift velocity is assumed to be directly proportional to the electric field strength (\ni\_e = \mu\_e E(y))
  - charge carrier lifetime is assumed to be constant \tau\_e = const.
  - in the case where the mean lifetime is much smaller than the time necessary to travel to the implants, there is a dependence of the CCE from the biasing voltage V
  - a fraction (\sim 0.5) of charge carriers recombines immediately after creation

# Simulation time & output data

- By default, Allpix2 outputs a small (\sim 3 MB) summary in ROOT format
  - It contains a list of predefined histograms to inspect each module (e.g. DepositionGeant4, GenericPropagation, etc.).
- If called, the module 'ROOTObjectWriter' record all the 'raw' simulation data in a ROOT file (size \sim 0.5 GB).
  - The summary report can be reconstructed by using ROOT macros.
  - Allpix2 symbols allow for a deeper analysis using the 'raw' data
- Simulation bottleneck is in the file I/O:
  - summary only (\sim 4 minutes)
  - with 'raw' root file (\sim 3.3 days)
- It is important to set the quantities of interest, in order to optimize simulation time by reducing file IO. For instance I focused over observables for studying the CCE; charge recombination; and the best operating conditions

### **Preliminary results**



Fraction of recombined charge carriers



In each step, charge carrier lifetime (\tau) is determined and a survival probability is calculated: a random O\leq r \leq 1 is compared with dt / \tau with dt the time step of the last charge carrier movement